

WHAT IS CLAIMED IS:

1. A resist removing composition comprising:

alkoxy N-hydroxyalkyl alkanamide; and

a swelling agent.

2. The resist removing composition of claim 1, wherein the alkoxy

N-hydroxyalkyl alkanamide is represented by a formula,



wherein R_1 is one of a hydrogen atom and a C_1 to C_5 hydrocarbon, and R_2 , R_3 and R_4 are independently C_1 to C_5 hydrocarbons.

3. The resist removing composition of claim 1, wherein the alkoxy

N-hydroxyalkyl alkanamide comprises about 10 wt% to about 70 wt% with reference to a total weight of the resist removing composition.

4. The resist removing composition of claim 1, wherein the swelling

agent is a hydroxylamine salt.

5. The resist removing composition of claim 4, wherein the

hydroxylamine salt is one selected from the group consisting of hydroxylamine sulfate, hydroxylamine hydrochloride, hydroxylamine nitrate, hydroxylamine phosphate, hydroxylamine oxalate, hydroxylamine citrate, and mixtures thereof.

6. The resist removing composition of claim 4, wherein the hydroxylamine salt is hydroxylamine sulfate.
7. The resist removing composition of claim 1, wherein the swelling agent comprises about 0.01 wt% to about 30 wt% with reference to a total weight of the resist removing composition.
8. The resist removing composition of claim 3, wherein the swelling agent comprises about 0.01 wt% to about 30 wt% with reference to the total weight of the resist removing composition.
9. The resist removing composition of claim 6, wherein the swelling agent comprises about 0.01 wt% to about 30 wt% with reference to a total weight of the resist removing composition.
10. The resist removing composition of claim 1, further comprising a polar material having a dipole moment of 3 or greater.
11. The resist removing composition of claim 10, wherein the polar material is one selected from the group consisting of water, methanol and dimethyl sulfoxide.

12. The resist removing composition of claim 10, wherein the polar material comprises about 0.01 wt% to about 60 wt% with reference to a total weight of the resist removing composition.

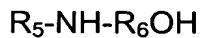
13. The resist removing composition of claim 1, further comprising an attack inhibitor.

14. The resist removing composition of claim 13, wherein the attack inhibitor is one selected from the group consisting of benzotriazole, catechol, gallic acid and an aliphatic carboxylic compound, and wherein the aliphatic carboxylic compound is one selected from the group consisting of acetic acid, citric acid, lactic acid and succinic acid.

15. The resist removing composition of claim 13, wherein the attack inhibitor is benzotriazole.

16. The resist removing composition of claim 13, wherein the attack inhibitor comprises about 0.01 wt% to about 30 wt% with reference to a total weight of the resist removing composition.

17. The resist removing composition of claim 1, further comprising alkanolamine represented by a formula,



wherein R_5 is one of a hydrogen atom and a C_1 to C_5 hydrocarbon, and R_6 is a C_1 to C_5 hydrocarbon.

18. The resist removing composition of claim 17, wherein the alkanolamine comprises about 0.01 wt% to about 30 wt% with reference to a total weight of the resist removing composition.

19. The resist removing composition of claim 1, comprising 10 to 70 wt% of the alkoxy N-hydroxyalkyl alkanamide and 0.01 to 30 wt% of a hydroxylamine salt as the swelling agent, and further comprising 0.01 to 60 wt% of a polar material having a dipole moment of 3 or greater.

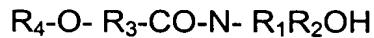
20. The resist removing composition of claim 19, further comprising 0.01 to 30 wt% of an attack inhibitor.

21. The resist removing composition of claim 19, further comprising 0.01 to 30 wt% of alkanolamine.

22. The resist removing composition of claim 1, wherein the resist is one selected from the group consisting of photoresist, polymer and organometallic polymer.

23. A method of removing resist, comprising:
providing a substrate having a resist layer formed thereon; and
contacting the substrate with a resist removing composition comprising
alkoxy N-hydroxyalkyl alkanamide and a swelling agent to remove the resist layer
from the substrate.

24. The method of claim 23, wherein during the contacting, the alkoxy
N-hydroxyalkyl alkanamide is represented by a formula,



wherein R_1 is one of a hydrogen atom and a C_1 to C_5 hydrocarbon, and R_2 , R_3 and
 R_4 are independently C_1 to C_5 hydrocarbons.

25. The method of claim 23, wherein the alkoxy N-hydroxyalkyl
alkanamide comprises about 10 wt% to about 70 wt% with reference to a total
weight of the resist removing composition.

26. The method of claim 23, wherein the swelling agent is a
hydroxylamine salt.

27. The method of claim 26, wherein the hydroxylamine salt is one
selected from the group consisting of hydroxylamine sulfate, hydroxylamine

hydrochloride, hydroxylamine nitrate, hydroxylamine phosphate, hydroxylamine oxalate, hydroxylamine citrate, and mixtures thereof.

28. The method of claim 26, wherein the hydroxylamine salt is hydroxylamine sulfate.

29. The method of claim 25, wherein the swelling agent comprises about 0.01 wt% to about 30 wt% with reference to a total weight of the resist removing composition.

30. The method of claim 23, further comprising a polar material having a dipole moment of 3 or greater.

31. The method of claim 30, wherein the polar material is one selected from the group consisting of water, methanol and dimethyl sulfoxide.

32. The method of claim 30, wherein the polar material comprises about 0.01 wt% to about 60 wt% with reference to a total weight of the resist removing composition.

33. The method of claim 23, further comprising an attack inhibitor.

34. The method of claim 33, wherein the attack inhibitor is one selected from the group consisting of benzotriazole, catechol, gallic acid and an aliphatic carboxylic compound, and wherein the aliphatic carboxylic compound is one selected from the group consisting of acetic acid, citric acid, lactic acid and succinic acid.

35. The method of claim 33, wherein the attack inhibitor is benzotriazole.

36. The method of claim 33, wherein the attack inhibitor comprises about 0.01 wt% to about 30 wt% with reference to a total weight of the resist removing composition.

37. The method of claim 23, further comprising alkanolamine represented by a formula,



wherein R_5 is one of a hydrogen atom and a C_1 to C_5 hydrocarbon, and R_6 is a C_1 to C_5 hydrocarbon.

38. The method of claim 37, wherein the alkanolamine comprises about 0.01 wt% to about 30 wt% with reference to a total weight of the resist removing composition.

39. The method of claim 23, comprising 10 to 70 wt% of the alkoxy N-hydroxyalkyl alkanamide and 0.01 to 30 wt% of the hydroxylamine salt as the swelling agent, and further comprising 0.01 to 60 wt% of a polar material having a dipole moment of 3 or greater.

40. The method of claim 39, further comprising 0.01 to 30 wt% of an attack inhibitor.

41. The method of claim 39, further comprising 0.01 to 30 wt% of alkanolamine.